	Hits	Search Text	DBs
1	2	((wafer or substrate or device) same (photosensitive or photoresist or resist) same (expos$4 or illuminat$4 or irradiat$4)) and ((light or radiation or illuminat$4) same (mirror near16 array) same (pluralit$4 or multiple) same piston same interference)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	6	((wafer or substrate or device) same (photosensitive or photoresist or resist) same (expos$4 or illuminat$4 or irradiat$4)) and ((light or radiation or illuminat$4) same (mirror near16 array) same (pluralit$4 or multiple) displac$6 same interference) and (piston same (pluralit$5 or multiple) same (irradiat$4 or illuminat$4 or light))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
3	7	((wafer or substrate or device) same (photosensitive or photoresist or resist) same (expos$4 or illuminat$4 or irradiat$4)) and ((light or radiation or illuminat$4) same (mirror near16 array) same (pluralit$4 or multiple) displac$6 same interference) and (piston same (pluralit$5 or multiple) same array)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
4	16	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and ((mirror near16 array) same (pluralit$4 or multiple) displac$6 same interference) and (piston same (pluralit$5 or multiple))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
5	6	(wafer or substrate or device) and (mirror same tilt$4) and (piston same (pluralit$5 or multiple) same (displac$6 or interference)) and modulat$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	8	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and ((mirror near16 array) same tilt$4) and (piston same (pluralit$5 or multiple)) and modulat$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
7	26	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and ((mirror near16 array) same tilt$4) and ((piston or adjust$4) same (pluralit$5 or multiple)) and (modulat$4 or SLM) and interference	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	5	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and ((mirror near16 array) same tilt$4) and ((piston or adjust$4) same (pluralit$5 or multiple)) and (modulat$4 or SLM) and interfer$5 and (displac$6 near22 mirror) and (phase$4 near16 (difference or shift$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
9	5	(wafer or substrate or device) and (photosensitive or photoresist or resist) and ((mirror near16 array) same tilt$4) and ((piston or adjust$3) same (pluralit$5 or multiple)) and (modulat$4 or SLM) and interfer$5 and (displac$6 near22 mirror) and (phase$4 near16 (difference or shift$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	12	(wafer or substrate or device) and (photosensitive or photoresist or resist) and ((mirror near16 array) same (torsion$4 or tilt$4)) and ((piston or adjust$3) same (mirror or DMD)) and (modulat$4 or SLM) and interfer$5 and (displac$6 near22 mirror) and (phase$4 near16 (difference or shift$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
11	14	(wafer or substrate or device) and (photosensitive or photoresist or resist) and ((mirror near16 array) same (torsion$4 or tilt$4)) and piston and (modulat$4 or SLM) and interfer$5 and (phase$4 near16 (difference or shift$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	18	((mirror near16 array) same (torsion$4 or tilt$4)) and piston and (modulat$4 or SLM) and interfer$5 and (phase$4 near16 (difference or shift$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
13	11	(modulat$4 same mirror same (torsion$4 or tilt$4) same (light or radiation or laser)) and ((piston or adjust$2r) same modulat$4) and interfer$5 and (phase$4 near16 (difference or shift$4)) and (mirror same (displace$4 or position$6))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	8	(modulat$4 same $6mirror same (torsion$4 or tilt$4) same (light or radiation or laser)) and ((piston or adjust$2r) same modulat$4) and interfer$5 and (phase$4 near16 (difference or shift$4)) and $6mirror and (displace$4 or $4position$6 or (path near12 length))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	15	(modulat$4 same $6mirror same (torsion$4 or tilt$4 or angle) same (light or radiation or laser)) and ((piston or adjust$2r) same modulat$4) and interfer$5 and (phase$4 near16 (difference or shift$4)) and $6mirror and (displace$4 or $4position$6 or (path near12 length))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
16	13	($8mirror same (torsion$4 or tilt$4 or angle) same (light or radiation or laser)) and ((piston or adjust$2r) same (optical or mirror)) and interfer$5 and diffract$6 and ((phase$4 near16 (difference or shift$4 or profile or modulat$4)) same degree) and $8mirror and (displac$6 or $4position$6 or (path near12 length))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
17	0	($8mirror same (torsion$4 or tilt$4 or angle)) and ((piston or adjust$2r) same (optical or mirror or modulat$4 or (optical near9 element) or DOE)) and interfer$5 and diffract$6 and ((phase$4 near16 (difference or shift$4 or profile or modulat$4)) same degree) and $8mirror and (displac$6 or $4position$6 or (path near12 length)) and (modualt$5 same (light or laser or radiation))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	21	($8mirror same (torsion$4 or tilt$4 or angle)) and ((piston or adjust$2r) same (optical or mirror or modulat$4 or (optical near9 element) or DOE)) and interfer$5 and diffract$6 and ((phase$4 near16 (difference or shift$4 or profile or modulat$4)) same degree) and $8mirror and (displac$6 or $4position$6 or (path near12 length)) and (modulat$5 same (light or laser or radiation))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
19	10	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and (mirror same tilt$4) and ((piston or adjust$4) same (pluralit$5 or multiple) same resolution) and (modulat$4 or SLM) and interference	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
20	0	((wafer or substrate or device) same (photosensitive or photoresist or resist)) and (mirror same tilt$4) and (piston same (pluralit$5 or multiple) same resolution)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
21	9	(mirror same tilt$4) and (piston same (pluralit$5 or multiple) same resolution)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
22	56	(($8mirror or DMD or MEMS or SLM) same (torsion$4 or tilt$4) same (phase$4 near16 (difference or shift$4)) same degree)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	10	(($8mirror or DMD or MEMS or SLM) same (torsion$4 or tilt$4) same (phase$4 near16 (difference or shift$4)) same degree) and ((wafer or substrate or target) same (photosensitive or photoresist or resist) same (expos$4 or illuminat$4 or irradiat$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	18	(piston same (optical or mirror or modulat$4 or (optical near9 element) or DOE) same (phase$4 near16 (difference or shift$4)) same degree) and (displac$6 or $4position$6 or (path near12 length))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
25	22	(piston same (phase$4 near16 (difference or shift$4)) same degree) and ((wafer or substrate) same (photosensitive or resist or photoresist))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB